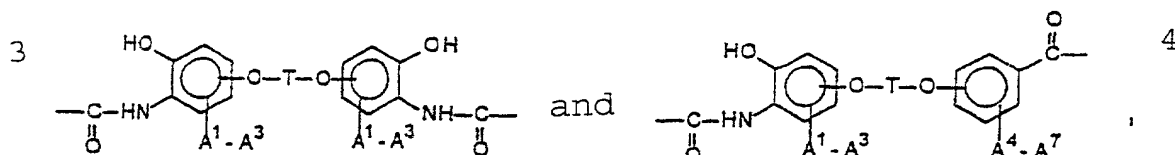


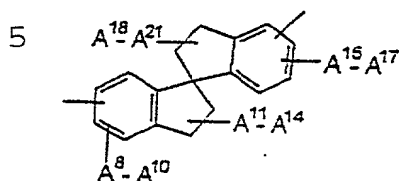
We Claim:

1. A polybenzoxazole precursor comprising a partial structure selected from the group consisting of

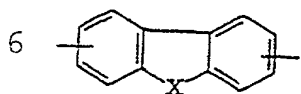


wherein each of A¹ to A⁷ is a univalent substituent independently selected from the group consisting of H, F, CH₃, CF₃, OCH₃ and OCF₃;

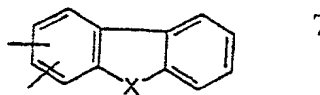
T is a residue selected from the group consisting of



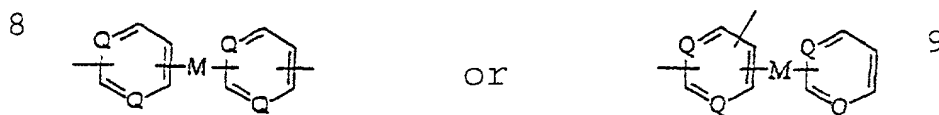
wherein each of A⁸ to A²¹ is a univalent substituent independently selected from the group consisting of H, F, CH₃, CF₃, OCH₃ and OCF₃;



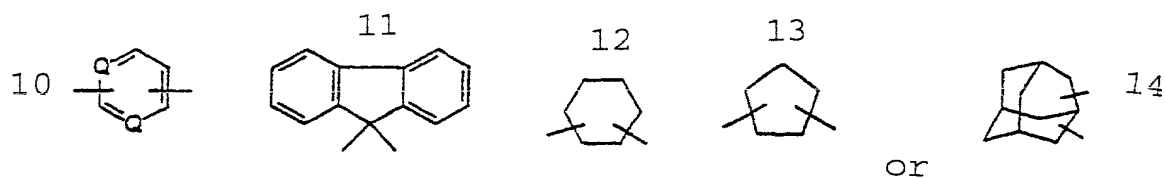
or



wherein X is selected from the group consisting of -CH₂-, -CF₂-, -C(CH₃)₂-, -C(CF₃)₂-, -C(OCH₃)₂-, -C(OCF₃)₂-, -C(CH₃)(C₆H₅)-, -C(C₆H₅)₂-, -O-, -(NH)-, -(N-CH₃)- and -(N-C₆H₅)-

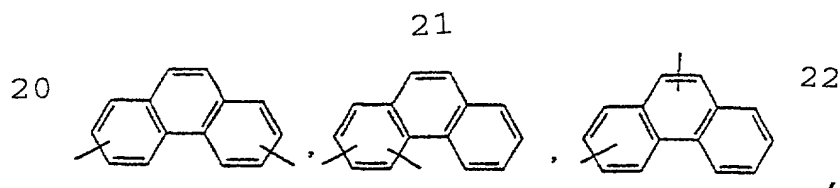
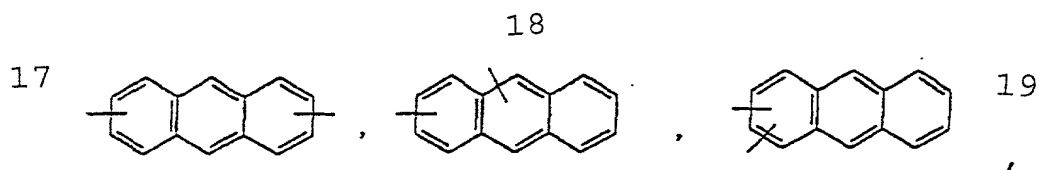


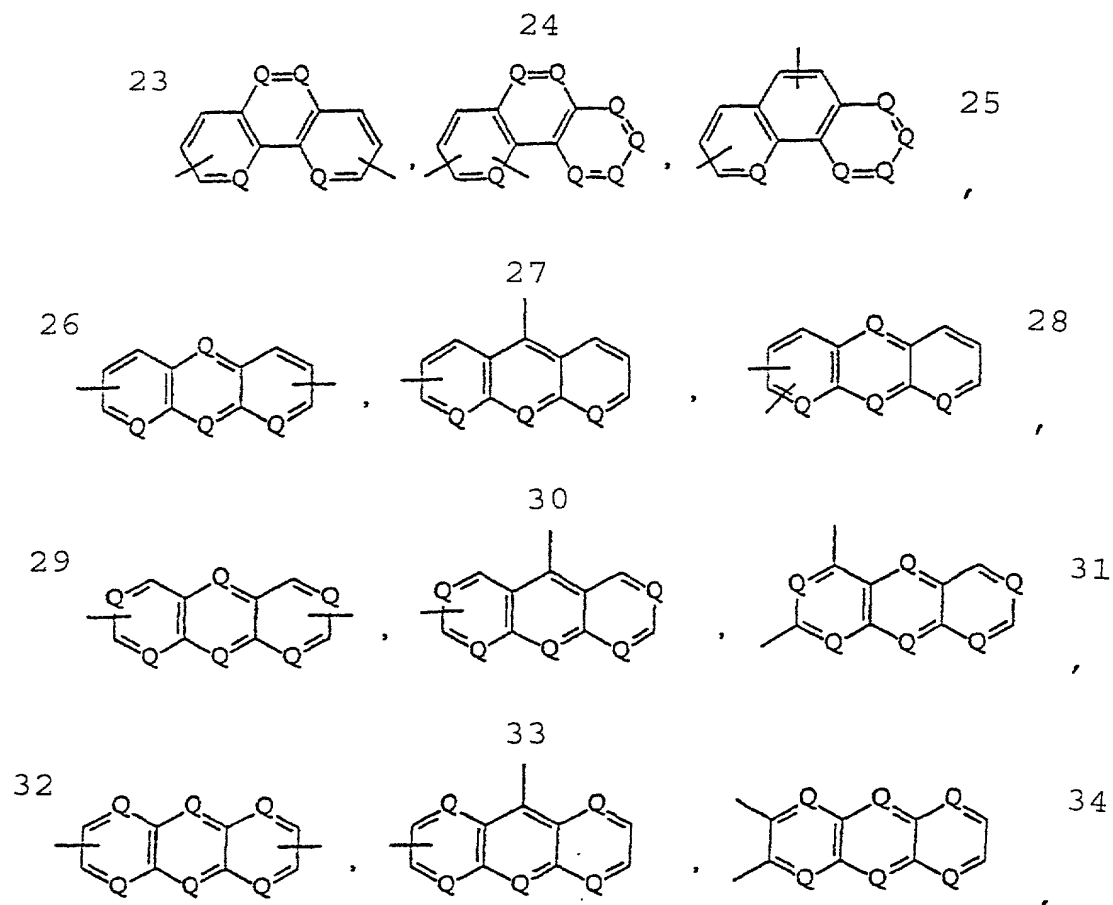
wherein M is selected from the group consisting of residues represented by formulas 10-14



in which Q is selected from the group consisting of C-H, C-F, C-CH₃, C-CF₃, C-OCH₃, C-OCF₃ and N,

and residues represented by formulas 15-34 shown below:





wherein Q is defined as above, provided that at least one Q signifies N and a maximum of two N atoms are present per ring.

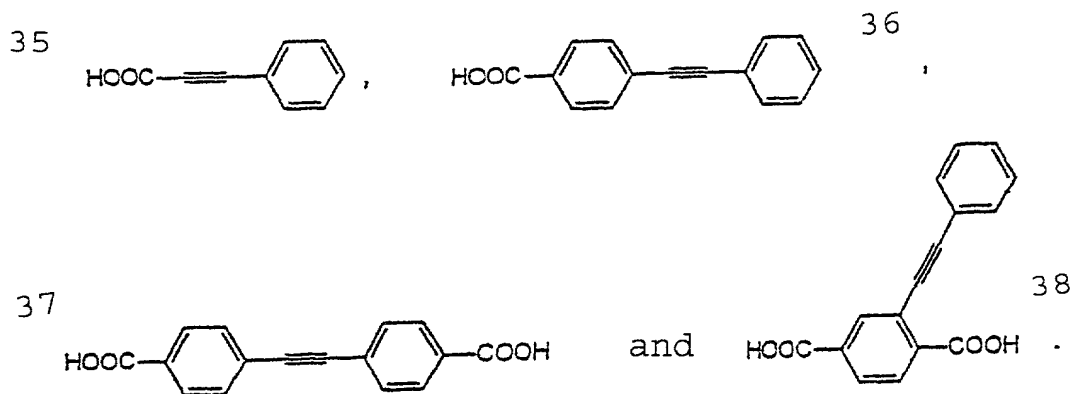
2. The polybenzoxazole precursor of claim 1, further comprising at least one acetylene group.

3. The polybenzoxazole precursor of claim 2, wherein said acetylene group is present in the main chain.

4. The polybenzoxazole precursor of claim 2, wherein said acetylene group is present in a side chain.

5. The polybenzoxazole precursor of claim 2, wherein said acetylene group is present in a chain terminating group.

6. The polybenzoxazole precursor of claim 2, wherein said acetylene group is present in the residue of a carboxylic acid selected from the group consisting of

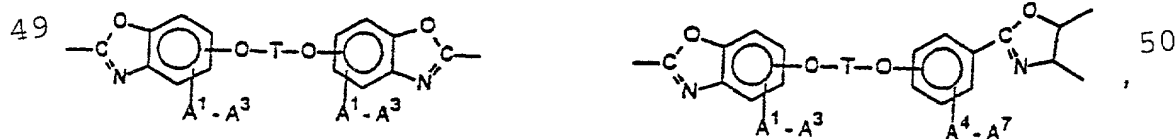


7. A photoresist solution, comprising a polybenzoxazole precursor of claim 1, a diazoketone photoactive component, and an organic solvent.

8. The photoresist solution of claim 7, wherein the weight ratio of polybenzoxazole precursor to diazoketone is in the range from 1:20 to 20:1.

9. The photoresist solution of claim 8, wherein a weight ratio of polybenzoxazole precursor to diazoketone is in a range from 1:10 to 10:1.

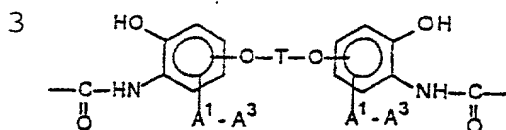
10. A polybenzoxazole containing a partial structure selected from the group consisting of



wherein each of A¹ to A⁷ is a univalent substituent independently selected from the group consisting of H, F, CH₃, CF₃, OCH₃ and OCF₃; and

T is a residue selected from the group consisting of the residues represented by formulas 5-34 defined above.

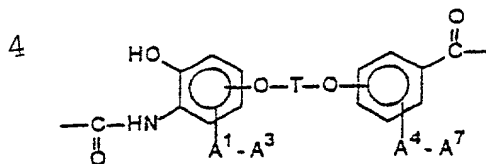
11. The polybenzoxazole precursor of claim 1, wherein said partial structure is



wherein each of A¹ to A³ is a univalent substituent independently selected from the group consisting of H, F, CH₃, CF₃, OCH₃ and OCF₃; and

T is a residue selected from the group consisting of the residues represented by formulas 5-34 defined above.

12. The polybenzoxazole precursor of claim 1, wherein said partial structure is

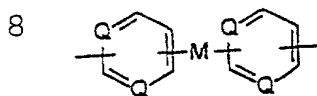


wherein each of A¹ to A⁷ is a univalent substituent independently selected from the group consisting of H, F, CH₃, CF₃, OCH₃ and OCF₃; and

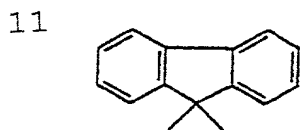
T is a residue selected from the group consisting of the residues represented by formulas 5-34 defined above.

13. The polybenzoxazole precursor of claim 1, wherein each of A¹ to A⁷ is H.

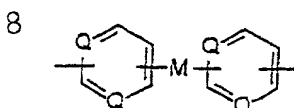
14. The polybenzoxazole precursor of claim 1, wherein T is



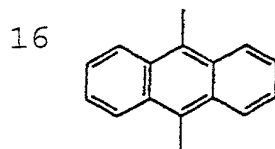
in which each Q is CH and M is



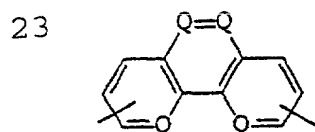
15. The polybenzoxazole precursor of claim 1, wherein T is



in which each Q is CH and M is

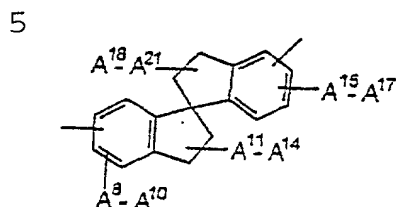


16. The polybenzoxazole precursor of claim 1, wherein T is



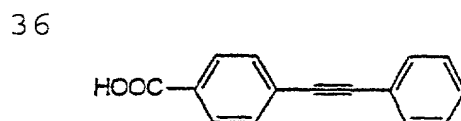
in which Q in each outside ring is N and each Q in the middle ring is CH.

17. The polybenzoxazole precursor of claim 1, wherein T is

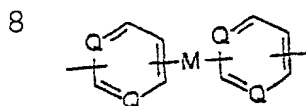


in which six of the substituents A⁸ to A²¹ are CH₃ and the remainder of the substituents A⁸ to A²¹ are H.

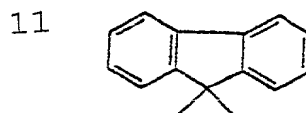
18. The polybenzoxazole precursor of claim 5, wherein said chain terminating group is a residue of



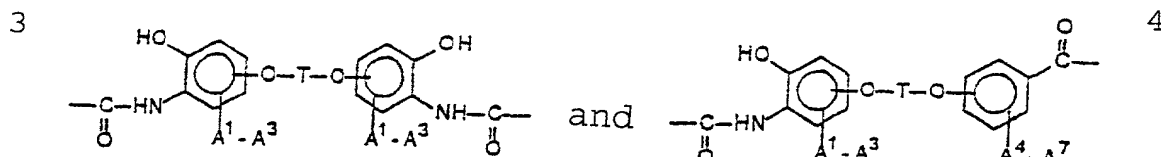
19. The polybenzoxazole precursor of claim 18, wherein T is



in which each Q is CH and M is



20. A process for preparing a polybenzoxazole precursor
containing a partial structure selected from the group
consisting of



wherein each of A¹ to A⁷ and T are as defined above, comprising
the steps of

providing at least one reactant selected from the group
consisting of bis-o-aminophenols and o-aminophenolcarboxylic
acids,

causing the reactant to react with at least one dicarboxylic
acid compound,

mixing the reaction mixture with a precipitating agent to
precipitate a solid polybenzoxazole precursor,

and isolating the polybenzoxazole precursor from the reaction mixture.

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